

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 2002-299300

(43)Date of publication of application : 11.10.2002

(51)Int.Cl.

H01L 21/304
B08B 3/02
B08B 3/08
B08B 3/12
H01L 21/308

(21)Application number : 2001-101039

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(22)Date of filing : 30.03.2001

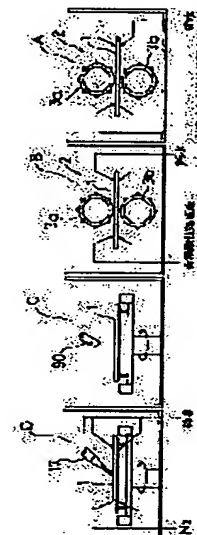
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(54) SUBSTRATE TREATMENT METHOD

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a substrate treatment method capable of completely removing contaminants stuck to the rear surface of a substrate without influencing the front surface of the substrate.

SOLUTION: The method has a first step A of treating the substrate 1 with organic alkaline treatment liquid, a second step B of treating the substrate 1 with organic acid treatment liquid after being treated by the first step A, a third step C of supplying high oxidizing power treatment liquid on the rear surface of the substrate 1 to clean it during rotation while supplying pure water on the front surface of the substrate 1 to form a liquid film after being treated by the second step B, and a step D of ultrasonically cleaning and drying the substrate 1 after being treated by the third step C.



LEGAL STATUS

[Date of request for examination] 29.03.2002

[Date of sending the examiner's decision of rejection] 18.02.2005

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

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